

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of	)	ATOMIC LAYER DEPOSITION
	)	METHOD AND SEMICONDUCTOR
Hwang et al.	)	DEVICE FABRICATING
	)	APPARATUS HAVING ROTATABLE
Application No.	)	GAS INJECTORS
	)	Group Art Unit:
Filing Date:	)	
		Examiner:

Commissioner for Patents  
P.O. Box 1450  
Mail Stop: Divisional Patent Application  
Alexandria, VA 22313-1450

**Amendment to the Specification:****--CROSS REFERENCE TO RELATED APPLICATION**

This application is a Divisional of U.S. patent application serial No. 09/927,004 entitled "ATOMIC LAYER DEPOSITION METHOD AND SEMICONDUCTOR DEVICE FABRICATING APPARATUS HAVING ROTATABLE GAS INJECTORS", filed on August 8, 2001 which claims the priority of Korean patent application serial No. 2000-46216, filed August 9, 2000.--